Amendments to the Claims:

This Listing of Claims represents the sole remaining claims in the Application. Briefly, previously presented claims 1-10 remain herein, following two restriction requirements, and the other claims, 11-75, are now cancelled, following withdrawal thereof by the Examiner in the latest Action.

Listing of Claims:

Claims 11 - 75 (cancelled). Please cancel Claims 11 - 75.

1. (previously presented). A method of making a circuitized substrate, said method comprising:

providing a first dielectric layer having a first surface;

forming a first pattern of conductors and a second pattern of conductors spaced from said first pattern and electrically coupled thereto on said first surface of said first dielectric layer;

forming a common conductive line on said first surface of said first dielectric layer electrically connected to each of said conductors of said second pattern of conductors; and

thereafter terminating said electrical connections between each of said conductors of said second pattern of conductors and said common conductive line using a laser.

2. (previously presented). The method of claim 1 further including positioning a second dielectric layer substantially over said first and second patterns of conductors prior to said terminating of said electrical connections.

- 3. (previously presented). The method of claim 2 wherein said second dielectric layer is provided in substantially liquid form and flowed onto said first dielectric layer.
- 4. (previously presented). The method of claim 3 wherein said second dielectric layer comprises a soldermask.
- 5. (previously presented). The method of claim 2 further including using said laser to simultaneously provide openings in said second dielectric layer above respective ones of said electrical connections during said terminating of said connections.
- 6. (previously presented). The method of claim 5 wherein said laser also partially removes some of said first dielectric layer immediately below said electrical connections during said terminating of said connections.
- 7. (previously presented). The method of claim 1 wherein said first and second pattern of conductors and said common conductive line are formed using electrolytic plating.
- 8. (previously presented). The method of claim 1 further including positioning a semiconductor chip on said first dielectric layer and electrically coupling said semiconductor chip to said first pattern of conductors.
- 9. (previously presented). The method of claim 8 wherein said electrically coupling of said semiconductor chip to said first pattern of conductors is accomplished using a wirebonding operation.
- 10. (previously presented). The method of claim 8 wherein said semiconductor chip is electrically coupled to said first pattern of conductors using a plurality of solder balls.